

ABSTRACT

An apparatus is developed for discharging a waste gas in a semiconductor (or TFT-LCD) manufacturing process. The present invention has its purpose to constantly set the amount of purge of nitrogen for inducing the waste gas to discharge while increasing a temperature of the waste gas so that dust of the waste gas is not accumulated on the inner wall of a pipe, and prevent an accident such as a burn from occurring in workers. The apparatus includes an inlet transfer 100 having an inlet port 102 and a support rib 104, a discharge transfer 140 having a support jaw 144 fixed to a support rib and forming a blow-off gap 110 along with the inlet transfer, a transfer cap 160 coupled to the top of the inlet transfer, while surrounding the discharge transfer, a heating casing 180 forming a heating room 182 and having a nitrogen inlet port 184, an electric heat wire 200 disposed within the heating room, and a temperature sensor 220 for controlling a temperature of the electric heat wire. The apparatus may further comprise a burn-preventing cap 240 surrounding a heating casing 180 with a given distance from the outer circumferential face of the heating casing.